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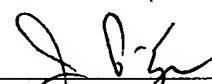


PATENT
30205/39513

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Young Sun Hwang et al.)
Serial No.: 10/719,083)
Filed: November 21, 2003)
For: Methods for Forming Fine)
Photoresist Patterns)
Group Art Unit: 1765)
Examiner: Patricia Ann George)
Confirmation No. 2261)

I hereby certify that this paper and the documents referred to as enclosed therewith are being deposited with the United States Postal Service as first class mail, postage prepaid, on January 13, 2006, in an envelope addressed to MS Amendments, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450



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Reg. No. 28,491
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AMENDMENT "A"

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Dear Sirs:

Please amend this application as follows:
the amendment to the claims section (along with a complete listing of claims) begins on page 2 of this paper;
the remarks section begins on page 4 of this paper.